What is Claimed Is:

- 1. A polishing apparatus comprising:
- a polishing tool;

a substrate holding member to hold a substrate and to press a surface of the substrate against said polishing tool, said substrate holding member including a guide ring for holding an outer periphery of the substrate; and

a first failure detection sensor for detecting a failure of the substrate inside of said guide ring, said first failure detection sensor being disposed at said substrate holding member or in the vicinity of said substrate holding member.

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- 2. The polishing apparatus according to claim 1, further comprising a second failure detection sensor for detecting a failure of the substrate under said guide ring.
- 3. The polishing apparatus according to claim 1, further comprising a second failure detection sensor for detecting a failure of the substrate outside of said substrate holding member.
- 4. The polishing apparatus according to claim 1, further comprising a second failure detection sensor for detecting a failure of the substrate under said guide ring, and a third failure detection sensor for detecting a failure of the substrate outside of said substrate holding member.

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- 5. The polishing apparatus according to claim 1, wherein said first failure detection sensor comprises a supersonic sensor.
- 6. The polishing apparatus according to claim 1, wherein said first failure detection sensor comprises a supersonic sensor to measure a distance between said supersonic sensor and an object or to measure a sound pressure from the object.
- 7. The polishing apparatus according to claim 1, wherein said first failure detection sensor comprises a radiation temperature sensor.

- 8. The polishing apparatus according to claim 1, wherein said first failure detection sensor is to detect a variation in electrostatic capacity of a condenser.
- 9. The polishing apparatus according to claim 1, wherein said first failure detection sensor has
  a piezoelectric element that is to abut the substrate.
  - 10. The polishing apparatus according to claim 1, further comprising a control unit to stop said polishing tool or said substrate holding member when said first failure detection sensor detects a failure of the substrate.

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- 11. A polishing apparatus comprising:
- a polishing tool;

a substrate holding member to hold a substrate and to press a surface of the substrate against said polishing tool; and

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at least two failure detection sensors for detecting a failure of the substrate in a radial direction of said substrate holding member.

12. The polishing apparatus according to claim 11, wherein said at least two failure detection sensors have a piezoelectric element that is to abut the substrate.

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13. The polishing apparatus according to claim 11, wherein said substrate holding member includes a guide ring for holding an outer periphery of the substrate, and wherein said at least two failure detection sensors are to detect a failure of the substrate inside of said guide ring.

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14. The polishing apparatus according to claim 11, wherein said substrate holding member includes a guide ring for holding an outer periphery of the substrate, and wherein one of said at least two failure detection sensors is to detect a failure of the substrate under said guide ring and the other of said at least two detection sensors is to detect a failure of the substrate inside of said guide ring.

- 15. A polishing apparatus comprising:
- a polishing tool;

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- a substrate holding member to hold a substrate and to press a surface of the substrate against said polishing tool;
- a first failure detection sensor for detecting a failure of the substrate inside of said substrate holding member; and
- a second failure detection sensor for detecting a failure of the substrate outside of said substrate holding member.
- 10 16. The polishing apparatus according to claim 15, wherein said substrate holding member includes a guide ring for holding an outer periphery of the substrate, and wherein said first failure detection sensor is to detect a failure of the substrate under said guide ring.
  - 17. The polishing apparatus according to claim 15, wherein said substrate holding member includes a guide ring for holding an outer periphery of the substrate, and wherein said first failure detection sensor is to detect a failure of the substrate inside of said guide ring.
    - 18. The polishing apparatus according to claim 15, wherein one of said first and second failure detection sensors has a contact member and a measuring system for measuring an electrical connection between said contact member and said polishing tool.
    - 19. The polishing apparatus according to claim 15, wherein said first failure detection sensor comprises a displacement sensor for measuring a variation in position of said substrate holding member.
    - 20. The polishing apparatus according to claim 15, wherein said first failure detection sensor comprises a vibration sensor, a distorsion sensor or a pressure sensor.

- 21. A polishing apparatus comprising:
- a polishing tool;

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- a substrate holding member to hold a substrate and to press a surface of the substrate against said polishing tool; and
  - a failure detection sensor for detecting a failure of the substrate;

wherein said failure detection sensor is a displacement sensor for measuring a variation in position of a top surface of said substrate holding member.